

# Electron Beam Lithography System

**130kV**

ポイントビーム電子線描画装置

## CABL - UH Series

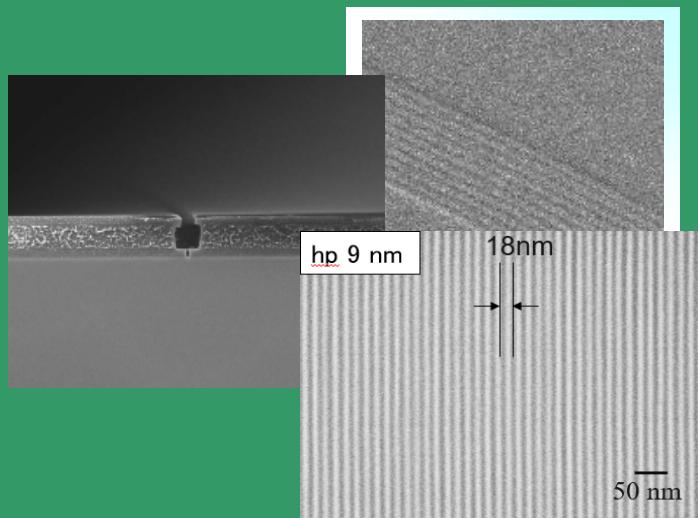
Next Generation High Performance Electron Beam Lithography Systems and Process Technology Solutions into the Future!



- <1.6nm Beam diameter
- <5nm fine line
- Single step acceleration
- 110keV, 90keV models available
- Ultra stable due to Double thermal control
- Double Permalloy shields

### Application

- Creation of new materials
- Quantum effect devices
- nano-devices
- Sub 5nm gaps



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